

# *Low Temperature Encapsulation for OLEDs and PLEDs*

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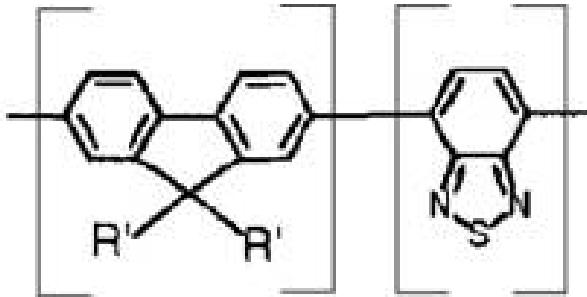
# Overview

- 1. PLED Devices**
- 2. Lifetime Issues**
- 3. Thin-Film Encapsulation of PLED Devices**
- 4. Polymer thin film encapsulation**
- 5. Inorganic thin film encapsulation by low-temperature PECVD of nitride and oxide films**

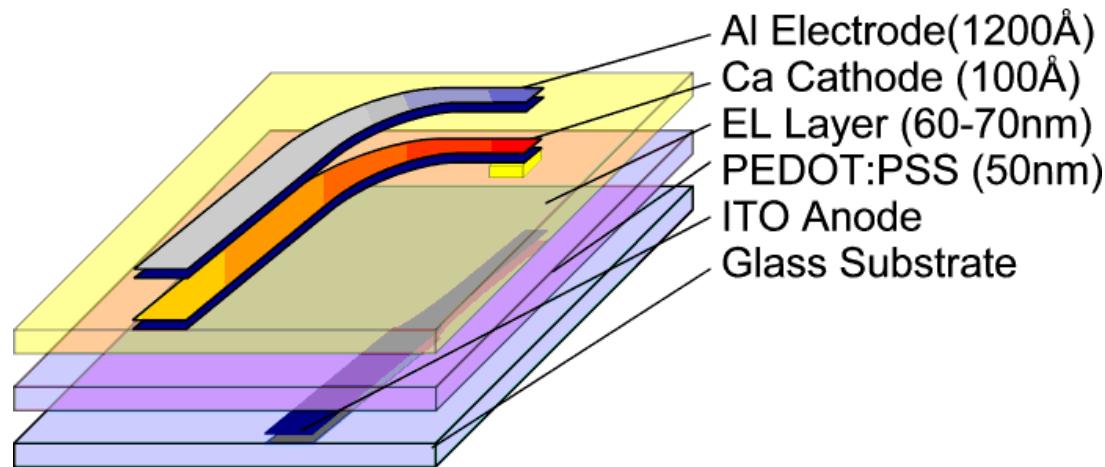


# *PLED with Green Polyfluorene*

- Dow Green
  - poly(9,9'-dioctylfluorene-alt-benzothiadiazole)



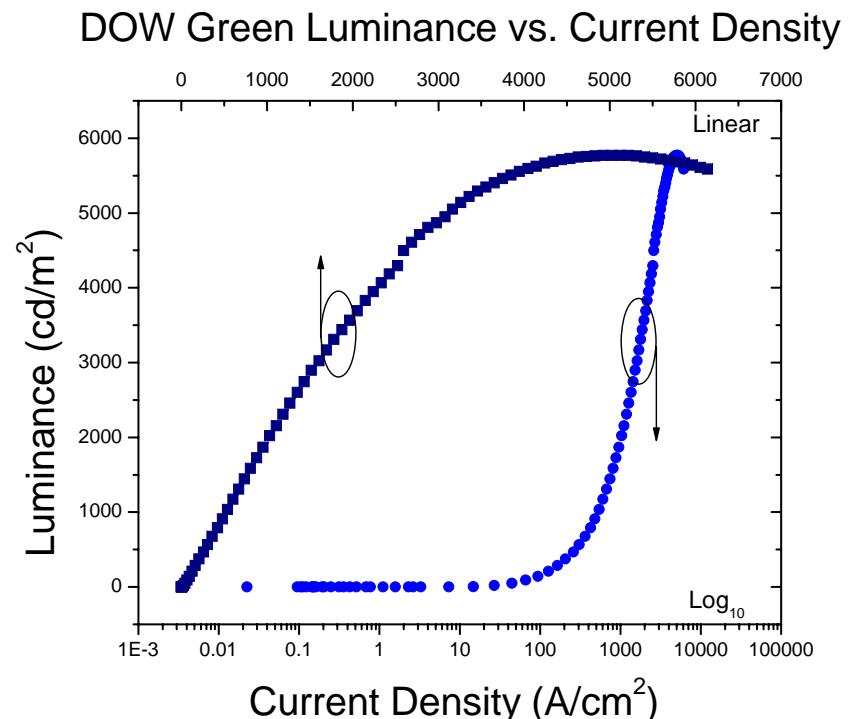
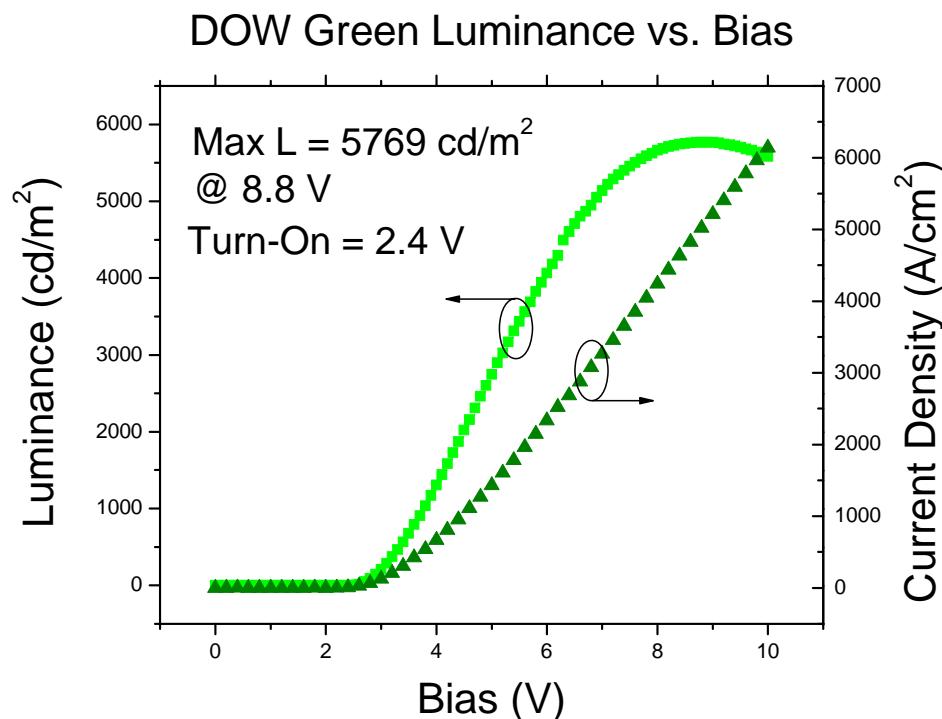
- ITO pre-patterned on glass or plastic
- Bilayer (PEDOT:PSS/EL) solution processable
- Thermally evaporated cathode (Ca/Al, Ca/Ag, Ca/Au, etc.)



# **Typical Characteristics of Dow Green OLED**

## **Solution:**

- 12 mg/mL xylenes



See Also:

J. Kanicki, S.-J. Lee, Y. Hong, C.-C. Su, Journal of the SID 13/12, pp. 993, 2005

M. T. Bernius, M. Inbasekaran, J. O'Brien, W. Wu, Adv. Mat. Vol. 12, No. 23, pp. 1737, 2000

Y. He, J. Kanicki, Proceedings of the SPIE, Vol. 4105, oo. 143, 2001



# ***OLED Lifetime***

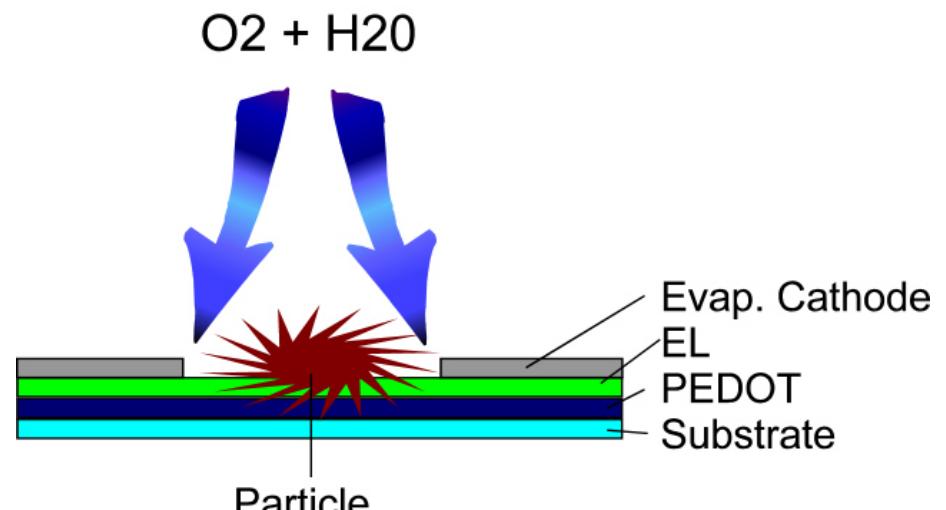
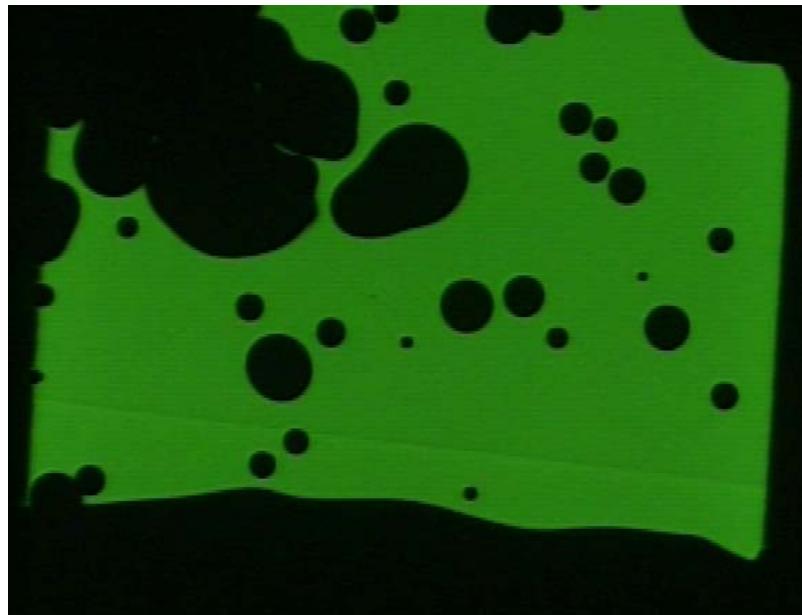
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- **Extrinsic Factors**
  - Oxygen and moisture diffusion
  - Growth of non-emissive regions (“dark spots”)
  - Presence of dust/particulate
    - Reduce luminance of the device
    - Reduce the usable time for use in solid state lighting or display applications
  - Joule heating
- **Intrinsic Factors**
  - Chemical instability
  - Redistribution of mobile ionic impurities



# Dark Spots

- **Dark Spot Formation**
  - Particulate Matter
  - Pinhole Defects
- **Dark Spot Growth**
  - Primarily due to cathode delamination
  - Nucleation occurs at organic/metal interface



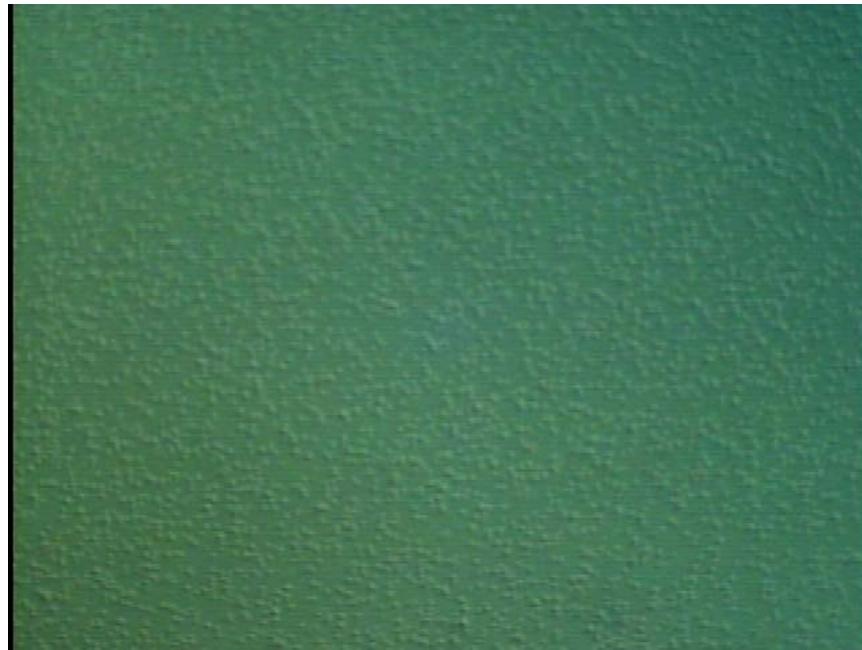
H. Aziz, Z. Popovic, C. P. tripp, N.-X. Hu, A.-M. Hor, G. Xu, App. Phys. Lett. Vol. 72, No. 21, 1998

K. K. Lin, S. J. Chua, S. F. Lim, J. App. Phys. Vol. 90, No. 2, pp. 976, 2001

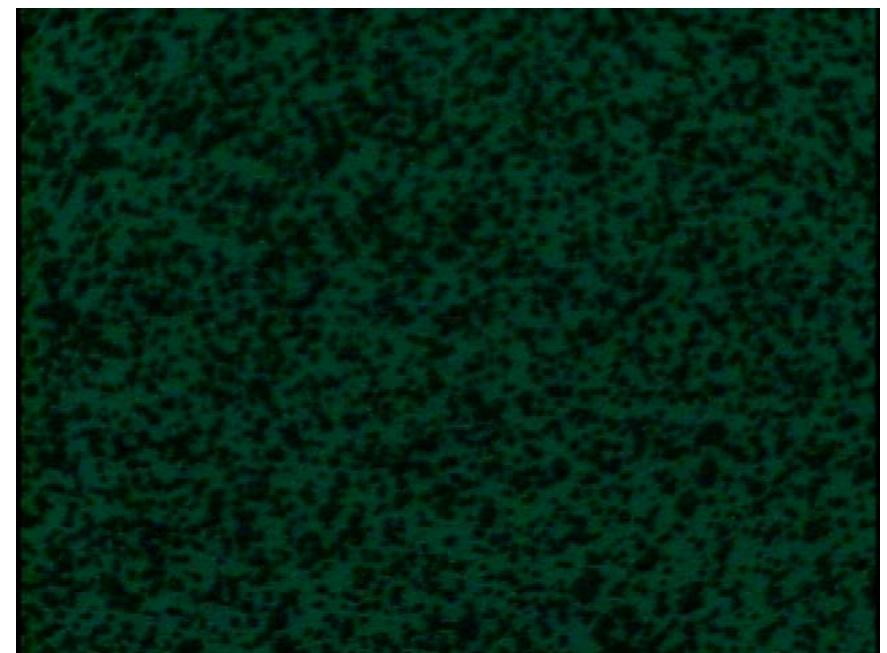
# ***Dark Spots from Poor Cathode Adhesion***

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**Delaminated regions result in non-luminescent area**



Device: OFF



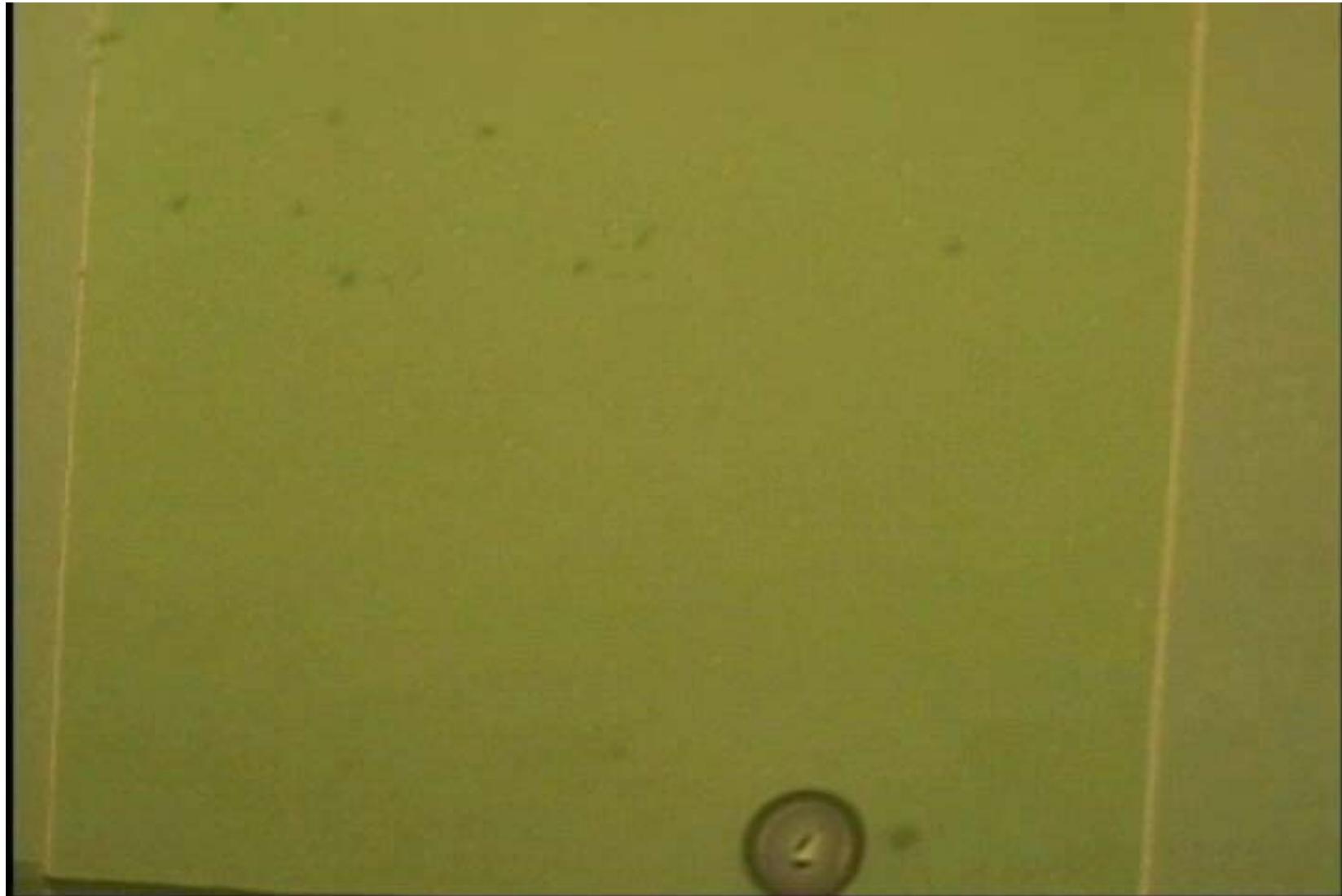
Device: ON



# *OLED Lifetime I (1 hr. 8 min. )*

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EL: DOW Green



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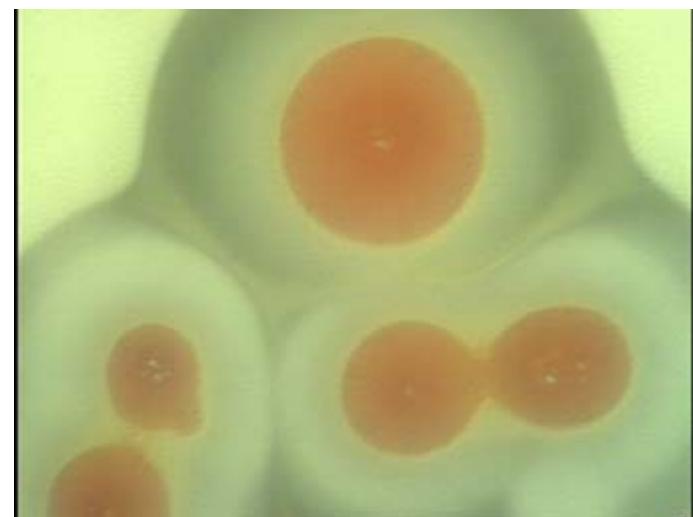
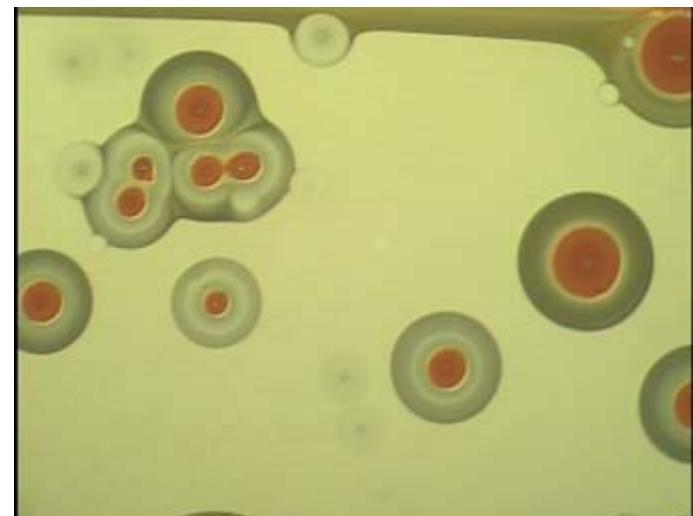
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## ***OLED Failure Details***

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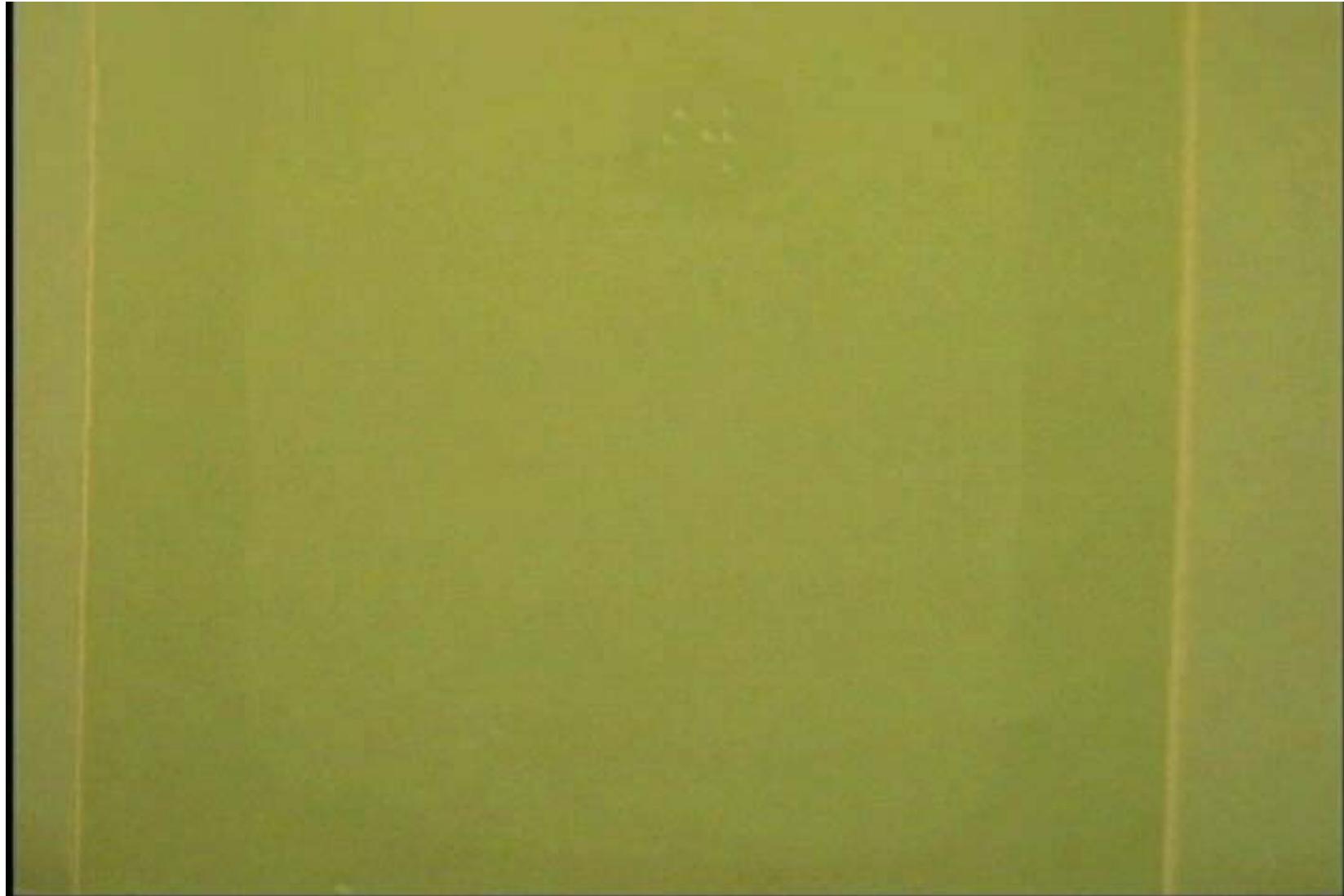
Images taken after “Lifetime I”  
video ended



# ***OLED Lifetime II (1 hr. 48 min.)***

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**EL: DOW Green**



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# ***PLED Encapsulation***

## Requirements

- **Good barrier to diffusion of O<sub>2</sub> and H<sub>2</sub>O**
  - WVTR: ~10<sup>-6</sup> g/m<sup>2</sup>-day
  - OTR: 1x10<sup>-5</sup> cm<sup>3</sup> (STP)/m<sup>2</sup>-day
- **Pinhole free**
- **Mechanically robust**
- **Commensurate with limitations of PLED devices**

## Encapsulation Methods

1. **Glass/Rigid cap**
  - Sealed with UV-curable epoxy
2. **Polymeric Film**
  - Spin-cast
3. **Inorganic Film**
  - SiNx, SiOx, AlOx
4. **Hybrid Approach**
  - Combination of 2 or more of the above

J. S. Lewis, M. S. Weaver, IEEE J. Sel. Top. Quan. Elec. Vol. 10, No. 1, pp. 45, 2004

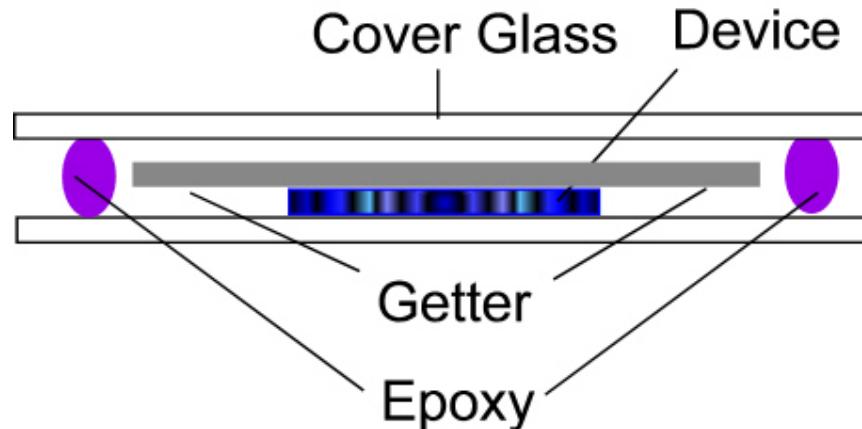
A. P. Ghosh, L. J. Gerenser, C. M. Jarman, J. E. Fornalik, Appl. Phys. Lett., Vol 86, pp. 223503, 2005

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# ***Rigid Glass Cap Encapsulation***

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## **Pro**

- Very good water and moisture barrier properties
- Transparent

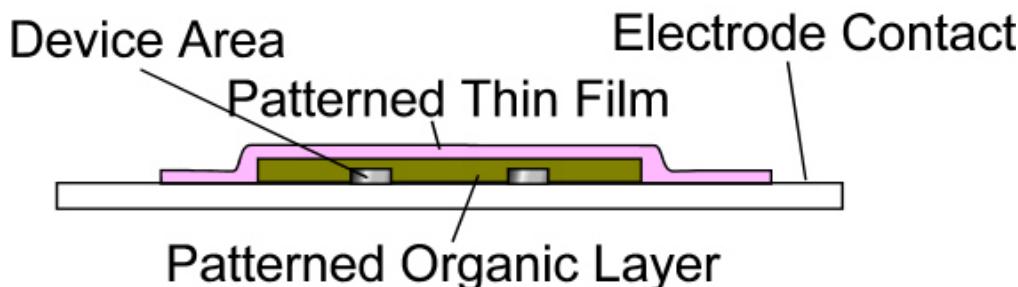
## **Con**

- Thick
- Rigid
- Requires the use of a getter
  - Unsuitable for top emission because opaque getter is placed on top of PLED device



# *Thin-Film Encapsulation - Polymers*

<u>Polymeric Films</u>	<u>Polymer</u>	<u>WVTR</u>	<u>OTR</u>
•Good Conformal coverage	Polyethylene	1.2-5.9	70-500
•Encases particulate matter to prevent formation of hole	Polypropylene	1.5-5.9	93-300
•Planarizes device	Polystyrene	7.9-40	200-540
•Ability to embed oxygen scavenging oxide particles in polymer matrix	PET	3.9-17	1.8-7.7
•Prone to oxygen and moisture diffusion	Poly(ethersulfone)	14	0.04
	PEN	7.3	3.0
	Polymide	0.4-21	0.04-17
	15nm Al/PET	0.18	0.2-2.9



*Permeability and Other Film Properties of Plastics and Elastomers*, 1<sup>st</sup> ed. Norwich, NY: Plastic Design Library (1995)

E. H. H. Jamieson, A. H. Windle, J. Mater. Sci. Bol. 18, pp. 64, 1983

E. Lueder, Electrochim. Soc. Proc. Vol. 98-22, pp. 1982, 1991

Y. Leterrier, Prog. In Mater. SCi, Vol. 48, pp. 1, 2003

J. S. Lewis, M. S. Weaver, IEEE J. Sel. Top. Quan. Elec. Vol. 10, No. 1, pp. 45, 2004



# *Thin Film Encapsulation – Inorganic Films*

## Inorganic Films

- **Low temperature PECVD processes for SiNx, SiO2**
  - IC systems “Low Temperature” considered 300-400C
  - Organic films require < 130C
- **Other low temperature processes available**
- **Dense films**

## Consequences of Low T

- Higher H Content → Lower Density
- More Pinholes

Assche et. al.: 3 SiNx layers, <100nm organic spacers

60C → WVTR =  $\sim 10^{-1}$  g/m<sup>2</sup>-day

100C → WVTR =  $\sim 10^{-4}$  g/m<sup>2</sup>-day

140C → WVTR =  $\sim 10^{-6}$  g/m<sup>2</sup>-day

$\text{SiN}_x$  n = 1.95-2.2 (Sparse – Dense) → 100C  $\text{SiN}_x$  n=  $\sim 1.8$  (experimental)

$\text{SiO}_x$  n = 1.46 – 1.96 (di – mono) → 100C  $\text{SiO}_x$  n=  $\sim 1.8$  (experimental)

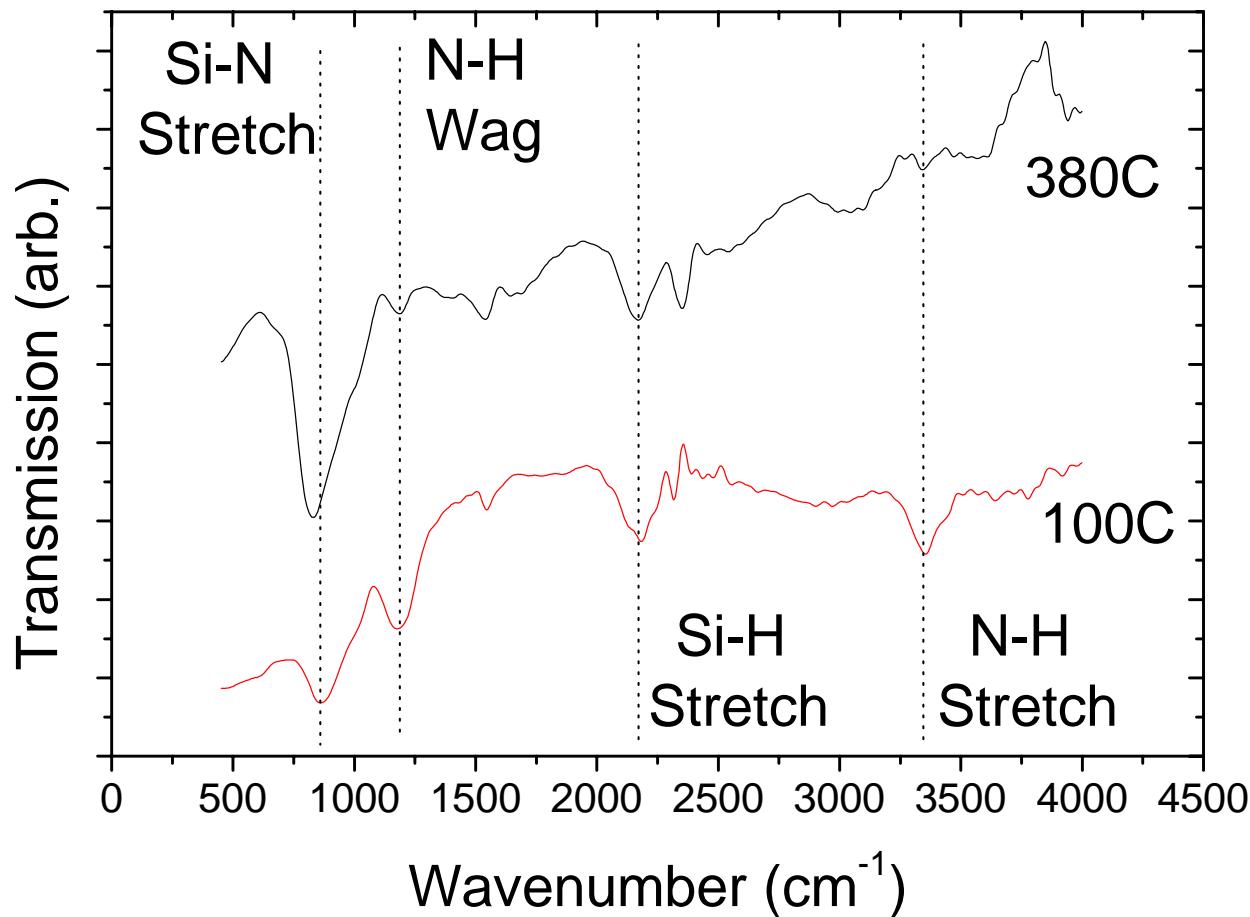
F. J. H. van Assche, R. T. Vangheluwe, J. W. C. Maes, W. S. Mischke, M. D. Bijker, F. C. Dings, M. F. J. Evers, W. M. M. Kessels, M. C. M. van de Sanden, SID 04 Digest, 695, 2004

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# ***Low Temperature Nitride FTIR***

PECVD SiNx at Low and High Temp

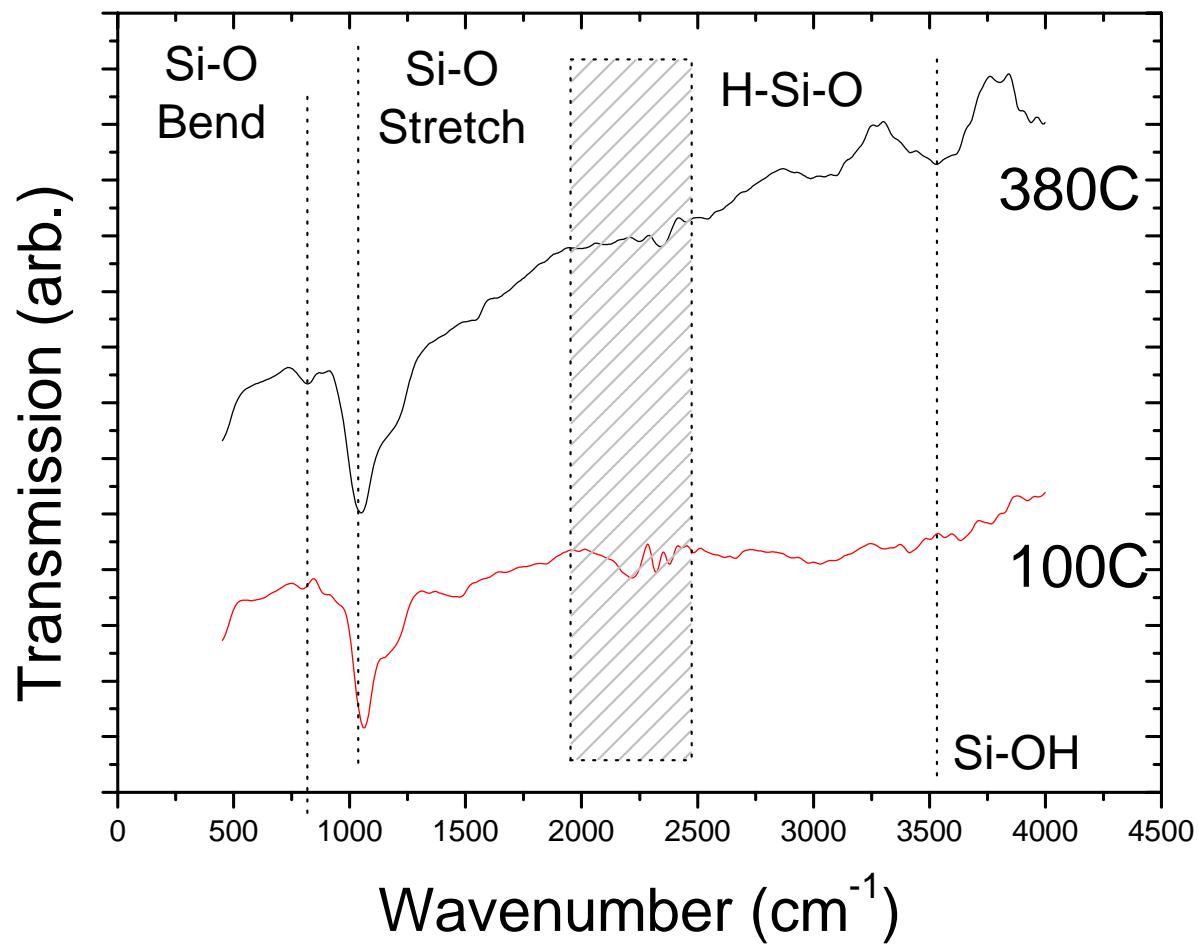


Significant enhancement of Si-H and N-H absorption indicating H-rich, less-dense films



# ***Low Temperature Silicon Oxide FTIR***

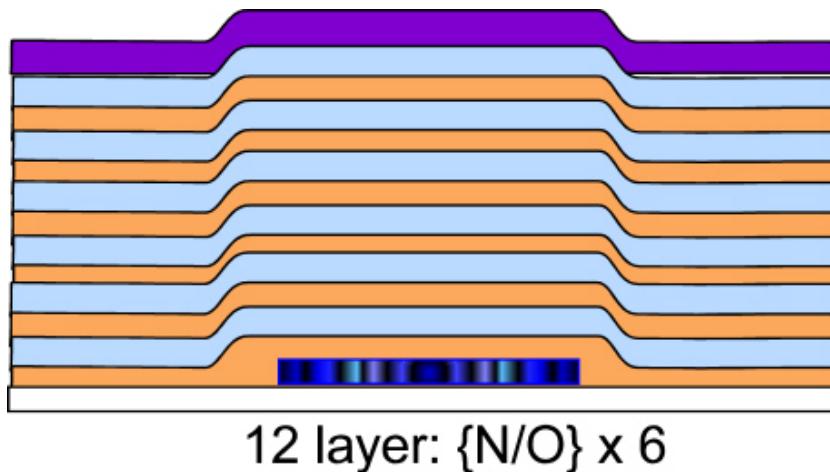
PECVD of SiO<sub>x</sub> at Low and High Temp



Small  
enhancement  
of H-Si-O  
absorption.  
No Si-OH  
absorption  
detectable



## *Thin-Film Encapsulation – Hybrid*



- 12-layer stack of alternating SiNx and SiOx
- Printed topcoat embeds particles in to scheme

{N/O} Stack	WVTR (g/m <sup>2</sup> -day)
5 Layers	$2.1 \times 10^{-3}$
12 Layers	$3.0 \times 10^{-5}$
5 Layers + topcoat	$1.6 \times 10^{-4}$
12 Layers + topcoat	$3.6 \times 10^{-6}$

J. J. W. M. Rosink, H. Lifka, G. H. Rietjens, A. Pierik, SID 05 Digest, pp. 1272, 2005

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# **Polymer-Based Oxygen Scavenger Layer**

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- **Ceramic oxide**
  - Particulate reactant phase is dispersed throughout a polymer matrix [1]
- **Amine-based Bairocade®**
  - Increases oxygen barrier of encapsulation schemes by almost 25x [2]
- **Mitsubishi offers an iron powder-filled polymer**
  - Shown to absorb 300cc of O<sub>2</sub> per gram of iron [3, 4]
- **Lucent copper particles suspended in a polymer matrix**
  - Shown to reduce corrosion [5]

***Active barrier films widely used in the food packaging industry***

[1] Higgins, L. M., Advancing Microelectronics, July/August, p. 6 (2003)

[2] PPG Industries Bairocade product information, [www.ppg.com/packaging](http://www.ppg.com/packaging).

[3] Mitsubishi Gas and Chemical, Product Information

[4] Vermeiren, L. et al., Rutgers University publication, Oct. 27, 2000,  
[www.foodsci.rutgers.edu/yam/packaging%20Network/Oxygen%20Scavenging%20Packaging.htm](http://www.foodsci.rutgers.edu/yam/packaging%20Network/Oxygen%20Scavenging%20Packaging.htm)

[5] Conservation By Design, Ltd., Corrosion Intercept technical Bulletin 11, "Corrosion of Copper," 1994.



# ***Conclusions***

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- **Degradation of PLED/OLED from dark spot formation and growth due to oxygen and moisture diffusion through pinhole defects in cathode**
- **Encapsulation of devices required for extended lifetime**
- **Optimized low temperature PECVD process for SiNx and SiOx produce porous, sparse films.**
- **Efficacy of these films enhanced with a hybrid approach**



## ***Typical Characteristics of Dow Green***

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